

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Huilong Zhu, et al.

Examiner: Chuong A. Luu

Serial No: 10/709,239

Art Unit: 2818

Filed: April 23, 2004

Docket: FIS920030375US1 (17192)

For: STRUCTURES AND METHODS FOR
MANUFACTURING OF DISLOCATION
FREE STRESSED CHANNELS IN BULK
SILICON AND SOI CMOS DEVICES BY
GATE STRESS ENGINEERING WITH
SiGe AND/OR Si:C

Dated: December 18, 2007

Confirmation No: 3238

Mail Stop Amendment
Commissioner for Patents
United States Patent Office
Alexandria, VA 22313-1450

RESPONSE UNDER 37 C.F.R. § 1.111

Sir:

In response to the Office Action dated September 18, 2007, Applicants submit the following remarks for entry of record in the above-identified patent application.

Amendments to the Claims are provided in the **Listing of Claims** beginning on page 2 of this paper.

Remarks begin on page 9 of this paper.

CERTIFICATE OF ELECTRONIC FILING

I hereby certify that this correspondence is being deposited with the United States Patent & Trademark Office via Electronic Filing through the United States Patent and Trademark Office e-business website, on **December 18, 2007**.

Dated: December 18, 2007


Steven Fischman